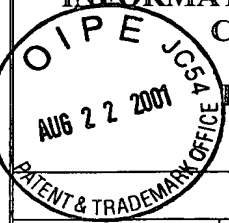
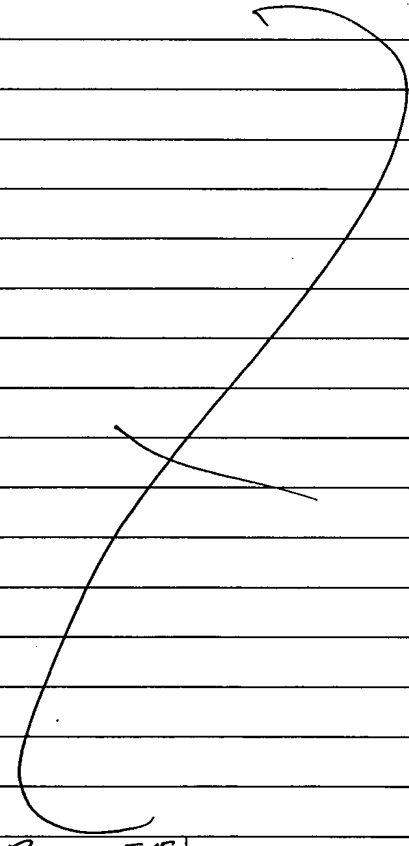
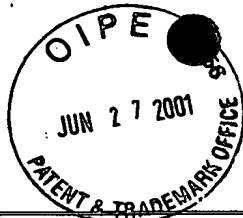


<b>INFORMATION DISCLOSURE CITATION</b> 		ATTY. DOCKET NO. 14912-777		SERIAL NO. 09/692,255											
		APPLICANT Savas, et al.													
		FILING DATE 10/19/00		GROUP <i>2811 1796</i>											
<b>U.S. PATENT DOCUMENTS</b>															
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE									
	4,393,092	07/12/1983	Gill	427	38	03/12/1982									
	5,292,370	03/08/1994	Tsai, et al.	118	723	08/14/1992									
	5,498,312	03/12/1996	Laermer, et al.	156	643.1	05/17/1994									
<b>FOREIGN PATENT DOCUMENTS</b>															
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<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>															
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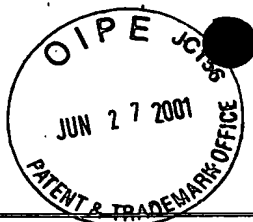
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SHEET 5 OF 5

INFORMATION DISCLOSURE CITATION  PTO-1449		ATTY. DOCKET NO. 14912.777		SERIAL NO. 09/692,255			
		APPLICANT Savas et al.					
		FILING DATE 10/19/2000		GROUP 2811 1796			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
ku	4,938,839	07/03/90	Fujimura et al.	156	628	10/11/88	
	4,857,140	08/15/89	Loewenstein	156	643	03/31/88	
	4,529,860	07/16/85	Robb	219	121 PE	08/02/82	
	4,501,061	02/26/85	Wonnacott	29	591	05/31/83	
ku	4,201,579	05/06/80	Robinson et al.	430	323	06/05/78	
FOREIGN PATENT DOCUMENTS							
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	A M ARLOFF			DATE CONSIDERED 3/23/03			

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SHEET 4 OF 5

INFORMATION DISCLOSURE CITATION  PTO-1449			ATTY. DOCKET NO. 14912.777		SERIAL NO. 09/692,255		
			APPLICANT Savas et al.				
			FILING DATE 10/19/2000		GROUP <del>281</del> 1746		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
AM	5,221,424	06/22/93	Rhoades	156	643	11/21/91	
	5,200,361	04/06/93	Onishi	437	194	10/08/91	
	5,200,031	04/06/93	Latchford et al.	156	659.1	08/26/91	
	5,198,634	03/30/93	Mattson et al.	219	121.43	05/21/90	
	5,174,856	12/29/92	Hwang et al.	156	643	08/26/91	
	5,057,187	10/15/91	Shinagawa et al.	156	643	05/18/90	
	5,037,506	08/06/91	Gupta et al.	156	646	09/06/90	
	4,980,022	12/25/90	Fujimura et al.	156	643	03/05/90	
AM	4,961,820	10/09/90	Shinagawa et al.	156	643	06/05/89	
FOREIGN PATENT DOCUMENTS							
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EXAMINER	A. MARDOFF		DATE CONSIDERED 3/23/03				

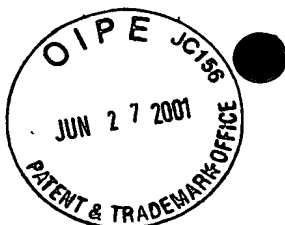
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SHEET 3 OF 5

INFORMATION DISCLOSURE CITATION  PTO-1449		ATTY. DOCKET NO. 14912.777		SERIAL NO. 09/692,255			
		APPLICANT Savas et al.					
		FILING DATE 10/19/2000		GROUP <del>281</del> 1746			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
RU ↑	5,362,358	11/08/94	Yamagata et al.	156	643	05/14/93	
	5,310,456	05/10/94	Kadomura	156	657	07/29/91	
	5,300,460	04/05/94	Collins et al.	437	225	03/16/93	
	5,294,292	03/15/94	Yamashita et al.	156	643	08/27/90	
	5,262,279	11/16/93	Tsang et al.	430	311	09/09/92	
	5,234,529	08/10/93	Johnson	156	345	10/10/91	
	5,228,052	07/13/93	Kikuchi et al.	373	18	09/11/91	
	5,227,341	07/13/93	Kamide et al.	437	229	02/06/92	
bu	5,226,056	07/06/93	Kikuchi et al.	373	18	01/09/90	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	D. MRRWOTT			DATE CONSIDERED 3/23/08			

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SHEET 2 OF 5

INFORMATION DISCLOSURE CITATION  PTO-1449			ATTY. DOCKET NO. 14912.777		SERIAL NO. 09/692,255		
			APPLICANT Savas et al.				
			FILING DATE 10/19/2000		GROUP <del>2811</del> 1746		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
B4	5,556,501	09/17/96	Collins et al.	156	345	04/01/93	
	5,534,231	07/09/96	Savas	216	67	01/17/95	
	5,514,247	05/07/96	Shan et al.	156	643.1	07/08/94	
	5,462,635	10/31/95	Ono et al.	216	67	05/31/94	
	5,451,293	09/19/95	Tabara	216	13	03/16/93	
	5,449,433	09/12/95	Donohoe	156	643.1	02/14/94	
	5,403,436	04/04/95	Fujimura et al.	156	643	07/11/94	
	5,393,374	02/28/95	Sato et al.	156	643	08/26/93	
B4	5,382,316	01/17/95	Hills et al.	156	643	10/29/93	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
	<del>L. Luo et al., "Systems and Methods for Variable Mode Plasma Enhanced Processing of Semiconductor Wafers," U.S. Patent Appln 09/192,810, filed 11/16/97</del>						
EXAMINER	A. MARRUPT			DATE CONSIDERED 3/23/02			

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SHEET 1 OF 5

INFORMATION DISCLOSURE CITATION		ATTY. DOCKET NO.		SERIAL NO.			
PTO-1449		14912.777		09/692,255			
		APPLICANT Savas et al.					
		FILING DATE 10/19/2000		GROUP <del>2811</del> 174 6			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
AM	6,068,784	05/30/00	Collins et al.	216	68	04/01/93	
	5,824,604	10/20/98	Bar-Gadda	438	725	01/23/96	
	5,811,022	09/22/98	Savas et al.	216	68	11/15/94	
	5,756,400	05/26/98	Ye et al.	438	710	12/08/95	
	5,747,387	05/05/98	Koizumi et al.	438	708	08/25/95	
	5,702,869	12/30/97	Chien et al.	430	313	06/07/96	
	5,691,117	11/25/97	Lutsic et al.	430	329	01/17/95	
	5,628,871	05/13/97	Shinagawa	438	514	06/24/94	
RM	5,567,271	10/22/96	Chu et al.	156	659.11	07/26/95	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
RM	H. Namatsu et al. "Hydrocarbon-Oxygen Mixture as a Resist Etching Gas with Highly Anisotropic Etching Feature," <u>Journal of Electrochemical Society</u> , Vol. 100, No. 2, Feb 1983, pp. 523-525						
	K. Hirose et al. "Ion-Implanted Photoresist and Damage-Free Stripping," <u>Journal of the Electrochemical Society</u> , Vol. 141, No. 1, Jan. 1994, pp. 192-205						
RM	<del>C. Ranft et al., "Downstream Surface Cleaning Process," U.S. Patent Appln 09/192,835 filed 11/16/98</del>						
EXAMINER <u>A. MARKOFF</u> DATE CONSIDERED <u>3/23</u>							

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